

4 Chamber Plasma System



Anatech's multi chamber system allows plasma processing of up to four samples at one time while avoiding cross contamination.

Applications:
Aashing
Failure Analysis
Surface Modification
Biological Sample Aashing
Geological Sample Aashing

4 Chamber Plasma System

Control System

Siemens S7-200 series PLC controller
Digital display for power, pressure, gas flow and time
Pass word protected
Gas Mass Flow Controller—1000 SCCM
Single gas input
Single process

Control Systems Options

Two program / two gases
Capacitance manometer
Slow pump and particle reduction
Throttle valve
Nitrogen Backfill

Reactor Chamber

System available with (2) or (4) chambers
4" Dia x 8" Quartz Chambers
Front loading
View port on front door with UV shield

RF Power Source

0-600 Watt, 13.56 MHz
Forward and reflected power reading
3% power regulation
Auto Match RF Tuner
Optional:
300 Watt 13.56 MHz supply
Low frequency optional

Power Requirements

115-VAC 15A 50/60-HZ
220-VAC optional
115-VAC 15A for Vacuum on separate

Dimensions

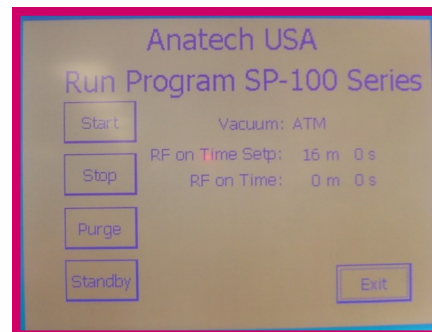
Cabinet Module:
23"W x 33"H x 30"D
Shipping Weight::
250 lbs Crated weight estimated

Vacuum Pump

23.3 CFM Standard—115 or 208V
Oxygen Preparation— Class "B"
Oil Mist Filter

Vacuum System Options

Corrosive service



**Siemens S7-200 Series
"Touch Panel" Control
Pass word protected**

CALL ANATECH USA TODAY TO DISCUSS YOUR APPLICATION

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